

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L4	1	laser interference confocal optic	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 09:36
L8	971	356/489,495,511-514.ccls.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 10:57
L10	12	8 and (laser or coherent or coherence) same interference same confocal	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 11:44
L12	10	(laser or coherent or coherence) same interference same confocal same defect not 4	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 11:53
L13	31	(laser or coherent or coherence) same interference same confocal same (glass or silicon dioxide or silica or SiO".sub.2") not 4	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 11:59
L14	1	12 and 13	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 11:50
L15	1	(laser or coherent or coherence) same interference same confocal same (surface roughness or RMS or root mean square near2 roughness) not 4 not 12	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 11:54
L16	1	13 and 15	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 11:54
L17	39	12 or 13 not 4 not 14 not 16	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 12:17
L18	7	(mask or photomask or reticle) same glass near2 (blank or base or substrate) same (polish\$3 or abra\$4 or grind\$3) same (colloid\$2) near2 (silica or silicon dioxide or SiO".sub.2")	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 13:48
L20	15	(mask or photomask or reticle) same glass same (blank or base or substrate) same (polish\$3 or abra\$4 or grind\$3) same (colloid\$2) same (silica or silicon dioxide or SiO".sub.2") not 18	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 14:09
L21	2785	((mask or photomask or reticle) near3 (phase or shift\$3 or reflect\$3 or extreme ultraviolet or extreme UV or EUV) or \$3PSM) same glass not 18 not 20	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 14:09

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L22	101	21 and glass same (polish\$3 or abra\$4 or grind\$3) same (silica or silicon dioxide or SiO".sub.2" or SiO\$6)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 14:12
L23	171	21 and glass same (polish\$3 or abra\$4 or grind\$3) not 22	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 14:12
L24	8570	430/5.ccls.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 14:13
L25	2089	24 and (mask or photomask or reticle) same glass same (blank or base or substrate) not 18 not 20 not 22 not 23	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 14:20
L26	608	21 and 25	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 14:20
L27	5	26 and (polish\$3 or abra\$4 or grind\$3) same (silica or silicon dioxide or SiO".sub.2" or SiO\$6) not 18 not 20 not 22 not 23	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 14:22
L28	8904	451/36,37,41,42,390.ccls. or 65/60. 1,61.ccls. or 427/160,165,290,292. ccls.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 14:23
L29	643	28 and (colloid\$2) same (silica or silicon dioxide or SiO".sub.2" or SiO\$6) not 18 not 20 not 22 not 23 not 27	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 14:24
L30	549	29 and (polish\$3 or abra\$4 or grind\$3) same (colloid\$2) same (silica or silicon dioxide or SiO".sub.2" or SiO\$6)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 14:25
L31	474	30 and (polish\$3 or abra\$4 or grind\$3) same (pressure or force or load)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 14:29
L32	68	31 and (pressure or force or load) same glass	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 14:30
L33	1462	51/308.ccls.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 14:34
L34	5	(30 or 33) and hydroly\$4 same (organosilicon or organo silicon or organic silicon or organic Si) same (colloid\$2) same (silica or silicon dioxide or SiO".sub.2" or SiO\$6) not 18 not 20 not 22 not 23 not 27 not 32	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 14:37

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L35	3	(30 or 33) and hydroly\$4 same (organosilicon or organo silicon or organic silicon or organic Si) not 18 not 20 not 22 not 23 not 27 not 32 not 34	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 14:38
L36	120	(30 or 33) and hydroly\$4 with (silica or silicon dioxide or SiO".sub.2" or SiO\$6) not 34 not 35	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 14:39
L37	8	36 and hydroly\$4 same (silicon or Si) with (organic or polymer)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 14:42
L38	7	36 and hydroly\$4 same (silicon or Si) same (organic or polymer) not 37	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 14:42
L39	17	(Kesahiro near2 Koike or Junji near2 Miyagaki).in. not 4 not 10 not 14 not 16 not 17 not 18 not 20 not 22 not 23 not 27 not 32 not 34 not 35 not 37 not 38	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 14:48
L40	1180	(polish\$3 or abra\$4 or grind\$3) same (colloid\$2) same (silica or silicon dioxide or SiO".sub.2") same (alkali metal or sodium or potassium or "Na" or "K") not 4 not 10 not 14 not 16 not 17 not 18 not 20 not 22 not 23 not 27 not 32 not 34 not 35 not 37 not 38 not 39	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 14:50
L41	99	33 and 40 and (colloid\$2) same (silica or silicon dioxide or SiO".sub.2") same (alkali metal or sodium or potassium or "Na" or "K")	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 14:51
L42	24	41 and (alkali metal or sodium or potassium or "Na" or "K") same impur\$5	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 14:52
L43	8	(glass and (mask or photomask or reticle) and (blank or substrate) and (polish\$3 or abra\$4 or grind\$3 or lap\$6) and (colloid\$2) and (silica or silicon dioxide or SiO".sub.2") and ("pH" or (protru\$4 or bulg\$3 or project\$3 or bump\$3) or surface roughness or (detect\$3 or inspect\$3 or measur\$5 or test\$3))).clm.	US-PGPUB; USPAT	ADJ	ON	2007/01/04 15:09
L44	781	430/4.ccls.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 15:11

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L45	0	(24 or 44) and (mask or photomask or reticle or \$3PSM) same (glass or quartz) same (blank or substrate) and (polish\$3 or abra\$4 or grind\$3 or lap\$6) same "pH" not 4 not 10 not 14 not 16 not 17 not 18 not 20 not 22 not 23 not 27 not 32 not 34 not 35 not 37 not 38 not 39 not 42 not 43	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 15:21
L46	5	(mask or photomask or reticle or \$3PSM) same (glass or quartz) same (blank or substrate) same (polish\$3 or abra\$4 or grind\$3 or lap\$6) same "pH" not 4 not 10 not 14 not 16 not 17 not 18 not 20 not 22 not 23 not 27 not 32 not 34 not 35 not 37 not 38 not 39 not 42 not 43	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 15:23
L47	1167639	glass	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 15:23
L48	247972	polish or polishing or polished	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 15:23
L49	443099	silica	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 15:24
L50	22417	47 and 48 and 49	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 15:24
L51	589887	"pH"	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 15:25
L52	7145	50 and 51	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 15:25
L53	6331	51 same 48	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 15:26
L54	1824	53 and 47 and 49	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 15:27
L55	31944	47 same 48	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 15:29
L56	1065	54 and 55	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 15:30

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L57	3010	48 near10 51	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 15:31
L58	669	56 and 57	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 15:31
L59	33984	colloidal silica	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 15:32
L60	328	58 and 59	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 15:32
L61	328187	glass.ti,ab.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 15:34
L62	71417	48.ti,ab.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 15:36
L63	70172	silica.ti,ab.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 15:36
L64	182	61 and 62 and 63	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 15:38
L65	7	(60 and 64) not 4 not 10 not 14 not 16 not 17 not 18 not 20 not 22 not 23 not 27 not 32 not 34 not 35 not 37 not 38 not 39 not 42 not 43 not 46	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 15:40
L68	69	48 same 59 same 47 same (silicon dioxide or SiO".sub.2") not 4 not 10 not 14 not 16 not 17 not 18 not 20 not 22 not 23 not 27 not 32 not 34 not 35 not 37 not 38 not 39 not 42 not 43 not 46 not 65	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 15:48
L69	6219	48 same pH not 4 not 10 not 14 not 16 not 17 not 18 not 20 not 22 not 23 not 27 not 32 not 34 not 35 not 37 not 38 not 39 not 42 not 43 not 46 not 65	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 15:48
L70	8	68 and 69	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 15:49

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L71	100	28 and (colloidal silica same (polish or polishing or polished) same "pH") not 4 not 10 not 14 not 16 not 17 not 18 not 20 not 22 not 23 not 27 not 32 not 34 not 35 not 37 not 38 not 39 not 42 not 43 not 46 not 65 not 70	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 15:54
L72	0	71 and (colloidal silica same (polish or polishing or polished) same pH) same glass	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 15:55
L73	20386	(quartz near3 glass) with (mask or photomask or reticle or substrate or blank or support)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 15:56
L74	6780	(mask or photomask or reticle) with (polish\$6 or lap\$6)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 15:57
L75	79	73 and 74 and excimer	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 16:26
L76	1215	(mask or photomask or reticle or substrate or blank or support) and ((pressure or weight\$6 or load) with ("kg/cm.sup.2" or "g/cm.sup.2")) same (polish\$6 or lap\$6)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 16:00
L77	39796	(polish\$6 or lap\$6) same (quartz or glass)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 16:02
L78	464	76 and 77	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 16:02
L79	39616	colloid\$6 near5 (silica or SiO".sub.2")	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 16:03
L80	1688	hydroly\$6 with 79	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 16:13
L81	8	78 and 80	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 16:25
L82	176	78 and 79 not 81	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 16:25
L83	1	75 and 82	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 16:32
L84	4	75 and 79 not 81 not 83	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 16:34

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L85	73	75 not 81 not 83 not 84	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 16:36
L86	2	76 and 85	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 16:41
L87	334	76 and 79 not 81 not 83 not 84 not 86	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 16:43
L88	175	87 and 77	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 16:43
L89	230	(glass or quartz) same (((pressure or weight\$6 or load) with ("kg/cm. sup.2" or "g/cm.sup.2")) same (polish\$6 or lap\$6))	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 16:57
L90	52	89 and 79	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 16:58
L91	31	90 and (surface roughness or root mean square or "RMS")	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 17:00
L92	53	88 and (surface roughness or root mean square or "RMS") not 91	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 17:00
L93	29	92 and pH	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/04 17:01